



BNL, IO-ASIC Activity

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Introduction

Expertise CAD/EDA Tools Mode of Operation Collaborations Areas of Activities



Expertise

Expertise in low-noise, low power, large mixed-signal designs

[≯] 11 full time ASIC designers + test leader



<u>amplifies linearly small input charge (⇒ Low noise)</u>





(⇒ better resolution)



simple bias (⇒ Low power)



13FI65P1 65 nm



●LArASIC_P4 180 nm

CALFE2 130 nm

•AVG_DEV 65 nm





HEXIDP1 65 nm

CAD/EDA Tools

Design tools and methodologies

 \mathbb{F} industry-standard tools from Cadence, Siemens (Mentor), etc. (analog on top or digital on top flows) analog: full custom flow (VSE, VLE, ADE/Spectre, AMS, PVS, XACT3D-PEX) digital RTL2GDS: functional simulation, logic synthesis, automated P&R, parasitics extraction, static timing analysis, HLS (XCELIUM/GENUS/INNOVUS/QUANTUS QRC/TEMPUS, Catapult/HLS Matlab) *library characterization:* custom standard cell libraries for designs for extreme environments: cryogenics, radiation, design for manufacturability and yield verification: IR drop (VOLTUS/ VOLTUS-fi), functional (SV), physical (PVS, Calibre DRC/ERC/LVS) device modeling: TCAD, FEM solvers, transistor model parameter extraction (Silvaco ATHENA-ATLAS-VICTORY, Maxwell,

UTMOTS4)

[∄] foundry PDK's: TSMC CMOS (from 180 nm to 28 nm), GF CMOS and BiCMOS SiGe 130nm, 90nm,

- 45 SPCLO + specialized processes: monolithic CIS on HR TPSCo, sensors co-design, XFAB High-Voltage bulk and PDSOI (180 nm and 110 nm) etc.
- access to foundries via: MOSIS, CERN-IMEC Foundry Services, DMEA/TAPO, IMEC and directly
- $\frac{3}{2}$ beyond Silicon: SiC process (ultra rad-hard)





pixel in 65 nm (G. Pinaroli)

Mode of Operation / Collaborations

Fast-developing scales and functionalities of modern μ electronics:

大 using established processes (130 nm, 65 nm) for projects ASIC in instruments 大 Special place: Monolithic Active Pixel Sensor (dedicated processes) 大 reaching for emerging technologies for R&D (28 nm, specialized processes)

Collaborations:

- 大 Universities: SMU, UMich, UPenn, MIT, Georgia Tech, Columbia, USF, UIUC, KU
- 太 National Laboratories: FNAL, LBNL, ORNL, NRL
- 1 Industry: several industrial partners + more collaborators
- 太 International: CERN, RAL, OMEGA, KIT Karlsruhe, AGH Krakow, UBonn



Areas of Activities 1

Areas of Activities and Research Interests:

Low-noise and low-power

- $\dot{\mathbf{x}}$ custom analog front-end matched to specific sensors
- 大 front-end circuits optimized for amplitude & time-resolution
- $\dot{\mathbf{x}}$ data, event driven or zero-suppressed readout methodologies
- 太 advanced processing AI/ML, highly-digital front-end

Cryogenic operation

- \pm readouts for Noble liquid TPCs R&D on RO electronics for DUNE's VD TPC, nEXO (IAr, IXe)
- $\dot{\mathbf{x}}$ long lifetime reliability
- 大 development & maintenance of spice-type model parameters and characterization (.lib) of standard cell libraries
- $\stackrel{-}{\longrightarrow}$ RF electronics for quantum sensors (4K, \leq 1K)

Photonics and interfaces

- 大 Power over Fiber (PoF)
- ☆ data transmission (energy efficiency)
- \pm photonic processors, including neuromorphic computing

V.Manthena et al, 2020 11th IEEE Annual 6 (UEMCON), 2020, pp. 0570-0576







probe station at CFN / cryostat at IO operating down to 4K

Areas of Activities 2

Radiation-Hardness

- Υ immunity to TID, NIEL and SEE effects:
 - process (inherent to process)
 - design (achieved through proper design techniques)
- Υ methodologies for SEE immunity
- \succeq exploration of next-gen for HEP CMOS and BiCMOS processes
- \cong Beyond Si (SiC for sensors and circuits)

Hybrid-pixel detectors

 \cong spectroscopic & imaging detectors for X-rays (BES, BER, NASA)

Monolithic Active Pixel Sensors

 \cong ePIC SVT and upgrades for the EIC (NP) and FCC

Lightweight detectors, 3D-IC and HDI

- \succeq edgeless and gapless, highly granular pixel detectors with extended functionalitie
- \succeq large area sensors for the EIC vertex and tracking layers
- Υ event-driven and neuromorphic suitable arrayed readouts

Embedded AI and neuromorphic processing

- \succeq co-design methodologies for FE ASICs
- \cong VMM processing with new electron devices: memristors





Examples of Projects

Cryogenic Low-Noise Front-End (DUNE, and beyond) Frameless, Configurable Readouts Advanced Pixel Detectors Monolithic Active Pixel Sensors Highly Digital and ML-Assisted Front-Ends





Cryogenic New Front-Ends 2

Experiment	Temperature	Detector Capacitance	Shaping Time	Noise	Dynamic Range
DUNE FD 3/4 charge readout	89 K – 300 K	150 pF – 200 pF	250 ns – 2 μs	500 e ⁻ at 87 K	10 bits
nEXO light readout	160 K – 300 K	5 nF	1 µs	0.1 pe⁻ at 160 K	10 bits
FCC-ee	TBD	TBD	< 250 ns	TBD	> 10 bits
PIONEER	160 K – 300 K	20 pF	20 ns	570 e ⁻ at 160 K	10 bits





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Brookhaven^T National Laboratory CHARMS250 and CHARMS10 are new developments

P. Mukim, et al, "Cryogenic Front-End ASICs for Low-Noise Readout₁₀ of Charge Signals", ready for submission for IEEE TCAS-I review

Frameless, Configurable Readout

National Laboratory



Advanced Pixel Detectors



Silicon-proven and patent pending;

D. Górni, WO/2022/221068: Event-Driven Readout System with non-priority arbitration for multichannel data

sources Brookhaven National Laboratory

number of readouts as intensity maps: as programmed using I2C-SPB interface



as actually

all pixels

read out from 3FI: Soft X-ray Spectroscopy

HEXID: Hard X-ray Space Telescope 12

Highly-Digital and ML-Assisted FE 1



Highly-Digital and ML-Assisted FE 2

Demonstration of feasibility

- \nexists channel height: 200 µm (including ADC)
- ∄ chip area: 5×5 mm²
- $\frac{3}{2}$ includes CML receiver for high-frequency input clock (8× f_s = 160 MHz).
- \nexists expected DSP power consumption ~10 mW/channel (clock = f_s = 20 MHz).
- ∄ design status: Currently being fabricated

Advantages for low-noise operation

- \nexists nonstationary filters (disabled during pulses)
- Itracking of pedestals / ch. (virtually infinite length, unrestricted windowing)
- \nexists inter-channel correlations (common mode)





non-achievable in pure analog processing !

MAPS ePIC SVT 1



- cables & services for µvertex & OuterBarrel layers
 + first 2 disks exite on a cone along 45° line and cables run in-front of MM
- 3 equal sized MM modules
- MM cables can run on front or back face of MM
- fewer sharp bends

G. Feofilov et al., ITS3 WP4 10 October 2023. Brookhaven⁻ National Laboratory



MPGD Barrels + Disks
 AC-LGAD based ToF



ePIC SVT detector layout configuration (in total almost 100B pixels, on \sim 10 m^2 of Si)

Silicon Barrel Layers							
		Radius [mm] (min, max)		Length [mm]	X/X0 [%]		
VX 1 (L0) 🛉		36		270	0.05		
VX2 (L1	l) IB	48	48 270		0.05		
VX3 (L2	2)	120	120 270		0.05		
Sagitta1 (L3)		270	270		0.25		
Sagitta2 (L4)		420		840	0.55		
Silicon Hadron Endcap (wheels)							
		Distance [cm]	Radius [mm] (min, max)		X/X0 [%]		
HD1		25	(36.76, 230)		0.24		
HD2	H-End	45	(36.76, 430)		0.24		
HD3	Сар	70	(38.42, 430)		0.24		
HD4	Disks	100	(54.43, 430)		0.24		
HD5	DISKS	135	(70.14, 430)		0.24		
Silicon Electron Endcap (wheels)							
ED1	E-End	-25	(3	6.76, 230)	0.24		
ED2		-45	(3	6.76 <i>,</i> 430)	0.24		
ED3	Сар	-65	(3	6.76, 430)	0.24		
ED4	DISKS	-90	(40.0614, 430)		0.24		
ED5		-115	(46	.3529, 430)	0.24		

Technology of choice: MAPS in TPSCo 65 nm process, following CERN's Disclaimer: ALICE ITS3 upgrade development of bent silicon some numbers, mainly X/X0, are evolving due to stave approach and cooling.



Some Further Investments

R&D for MAPS Data Transmission ps-level timing (28 nm) Handling SEU (word-level vs. TMR) Compound Semiconductors (SiC)



R&D for MAPS 1

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Power Management in Serial-Powering: Negative Voltage Generation for biasing sensor, $V_{NFG} \in$ negative (5-10 V)

x sensor bias is not serially powered ➡ positive to negative voltage required \wedge charge pump from positive supply

Digitally Controlled Duty Cycle Clock Clock Generator Oscillator Modulator SC Clk P SC Amplifier Offset Charge Pump (aux) Generator **RF** Driver Charge Pump (main) Feedback Amp

Vital-Function Monitoring ADC for Large-Area MAPS

 \times Self clocked with sequencer generating pausable clock, <5,000 μ m² 10 b ADC; Υ only connection to slow-control



G. W. Deptuch, "Charge-Sensitive Amplifier with Pole-Zero Cancellation" - patent pending

R&D for MAPS 2

Back-bone Transmission Line Encoding Driver (BTLE - Driver)

大 goal: transmit data across stitched sensor (~20 cm) at 160 Mb/s

大to avoid the use of repeaters at boundaries

大 high R and C density of metals severely limit bandwidth of wired links across RSUs



National Laboratory S. Mandal, G.W. Deptuch, A. Iqbal, "A Low-Power Data Link for Stitched Pixel Sensors", submitted for IEEE MWCAS conference / review

Instead of square wave, stream of synthesized analog symbols are sent \Rightarrow line encoding

21.666 m

X PADS ALDO DLDO

UNIT BIASING

DOMAIN

MATRIX

PADS ALDO

DOMAIN

MATRIX

UNIT BIASING

ADS ALDO DIDO

UNIT BIASING

DOMAIN

MATRIX

AUX PADS ALDO DLDO

UNIT BIASING

DOMAIN

MATRIX

10 833 mr

AUX PADS ALDO DLDO

UNIT BIASING

DOMAIN

MATRIX

3.611 mm

UNIT BIASING

DOMAIN

MATRIX

R&D for MAPS 3

Entirely Galvanically Isolated (GalIsol) detector system

- Y Power → by light on fiber (PoF) and PV cells;
- ✓ Slow Control and Reference Clock → delivered on fiber
- ✓ High-Speed data ← on fiber, wavelength multiplexed, EOM
 = Photonic IC (PIC)





Attractive for noble liquid detectors





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Decananometric process (28 nm)

Target application:

Fast-neutron radiography and tomography using Associated Particle Imaging (API) Deuterium-Tritium (D-T) neutron generators. Follow-up application:

AC-LGAD based TOF systems, e.g., for EIC



€ 24-channel, linear layout ASIC, aiming at $σ_t$ =~10-30 ps; € First step Front-End – Discriminator – Driver than development of TDC





28 nm Amplifier, TIA, Core: Cascoded Inverter+Gain Boosting, 200 MC Transient Noise @ C_{DET} =35 pF 1,200 μ A \rightarrow 795 μ W/ch \rightarrow 19.1 mW (24-channel ASIC)



SEU Mitigation... Comparison

Criteria	Word-Level Correction	Triple Modular Redundancy (TMR)		
Objectives	To detect and correct errors within individual words.	To ensure system reliability through redundancy and majority voting.		
Implementation Complexity	Can be high; requires complex encoding and decoding mechanisms for error correction.	Moderate; requires triplication of hardware and synchronization mechanisms. However, can leverage tools from HEP Community		
Resource Efficiency	Adds overhead for redundant bits.	Requires tripling hardware resources.		
Error Detection Capability	Can detect and correct single-bit and potentially multi-bit errors within words.	Can detect discrepancies across modules		
Error Correction Capability	Can automatically correct detected errors within the word limit.	Automatically selects the majority output, effectively correcting single-module faults.		
Latency/Performanc e Impact	Adds latency due to error detection and correction processing.	Adds latency due to the need for voting and possibly greater routing complexity.		



Compound Semi. Materials (sensors/ASICs)

Properties at 300K	Si	4H-SiC	Diamond	GaN
Atomic number (Z)	14	14/6	6	31/7
Density (g/cm³)	2.33	3.22	3.51	6.15
Relative permittivity, ε _r	11.9	9.7	5.7	9.6
Band gap energy, E _g (eV)	1.12	3.23	5.5	3.39
e-h pair creation energy, ε (eV)	3.6	7.6-8.4	13	8.9
e-h pair creation rate, MIP (eh/μm)	80	57	25	65
Displacement energy, E _d (eV)	13-15	20-35	43	10-20
Breakdown electric field, E _{max} (V/cm)	3 x 10 ⁵	3-4 x 10 ⁶	10 ⁷	4 x 10 ⁶
Electron mobility, μ _e (cm²/V.s)	1450	800-1000	1800-2200	1000
Hole mobility, µ _h (cm²/V.s)	450	50-115	1200-1600	30
Saturated e ⁻ drift velocity, v _{sat} (cm/s)	0.8 x 10 ⁷	2 x 10 ⁷	2.2 x 10 ⁷	1.4 x 10 ⁷
Thermal conductivity, κ (W/K.cm)	1.5	4.9	24-25	2.5

- Diamond has the best material properties but is difficult to use for implementing electronics.
- 4H-SiC is commercially available and has an excellent combination of material and electronic properties:
 - High band-gap: low dark current, insensitivity to low-energy photons
 - High charge production rate: high sensitivity
 - High displacement energy: radiation hardness
 - High breakdown electric field: high reverse bias voltages
 - High saturation velocity: fast signals, short transit times, low trapping probability



SiC MAPS for FCC-xx

- Bad news: Ecosystem for SiC integrated circuit (IC) fabrication is decades behind that of Si.
- Good news: The ecosystem is growing, and we already have an interested partner.
 - NASA Glenn Research Center (GRC), Cleveland, OH
 - GRC has developed two unique SiC IC processes: SiC-sensor and SiC-JFET
 - The SiC-JFET process has been used to develop many functional circuits for a future Venus mission
 - These circuits have been demonstrated to work for thousands of hours up to 900°C¹
 - Initial test results show excellent radiation hardness²

VDD

RST_SEL

VDD

ROW SEI

- We have been engaged in discussions with GRC for several months
 - Collaboration mechanism being set up

¹P. G. Neudeck, D. J. Spry, M. Krasowski, N. F. Prokop, and L. Y. Chen, in *Materials Science Forum*, 2019, vol. 963, pp. 813–817.

²J.-M. Lauenstein *et al.*, in 2019 IEEE Radiation Effects Data Workshop, 2019, pp. 1–7.





Summary

- ASIC / microelectronics efforts span broad spectrum of:
 - \bigstar applications

 - ⇐ technologies and techniques (electro-opto-mechanics)

• Topics

- ⇒ cryogenically operated FEs and readouts
- Hybrid Pixels and MAPS
- ➢ PoF and PICs (integrated photonics)
- edge processing and beyond-CMOS
- power management
- Jata conversion and transmission
- Jecananometric processes (28 nm)
- TOF and picosecond timing
- SiC as next level of radiation hardness

